

Resource Summary Report

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SUSS: MicroTek MA6/BA6 Mask Aligner

RRID:SCR_020533

Type: Tool

Proper Citation

SUSS: MicroTek MA6/BA6 Mask Aligner (RRID:SCR_020533)

Resource Information

URL: <https://www.suss.com/brochures-datasheets/mask-aligner-ma-ba-6.pdf>

Proper Citation: SUSS: MicroTek MA6/BA6 Mask Aligner (RRID:SCR_020533)

Description: MA/BA6 mask aligner is designed for all standard lithography applications and wafer sizes of up to 150 mm. For thick-resist MEMS applications, the MA/BA6 offers high resolution and optimum edge quality. The bottom side alignment option allows for pattern printing on both sides of the substrate. The MA/BA6 additionally provides tailored features for fragile III-V compounds, thinned or warped wafers, transparent substrates and pieces or single dies.

Resource Type: instrument resource

Keywords: SUSS Microtec, Mask Aligner, Instrument Equipment, USEDit

Availability: Commercially available

Resource Name: SUSS: MicroTek MA6/BA6 Mask Aligner

Resource ID: SCR_020533

Alternate IDs: Model_Number_MA6

Record Creation Time: 20220129T080350+0000

Record Last Update: 20260801T190652+0000

Ratings and Alerts

No rating or validation information has been found for SUSS: MicroTek MA6/BA6 Mask Aligner.

No alerts have been found for SUSS: MicroTek MA6/BA6 Mask Aligner.

Data and Source Information

Source: [SciCrunch Registry](#)

Usage and Citation Metrics

We have not found any literature mentions for this resource.